

Electronic Supplementary Information

Ni-P synergetic deposition: electrochemically deposited high active Ni as catalyst for chemical deposition

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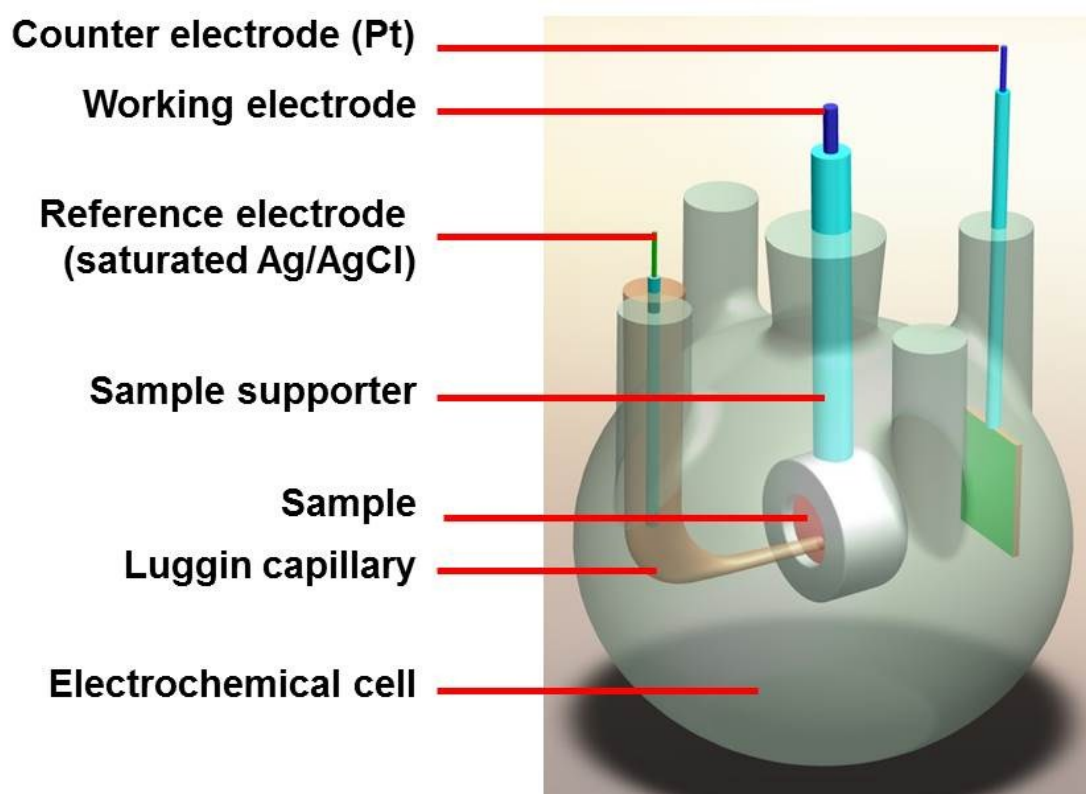
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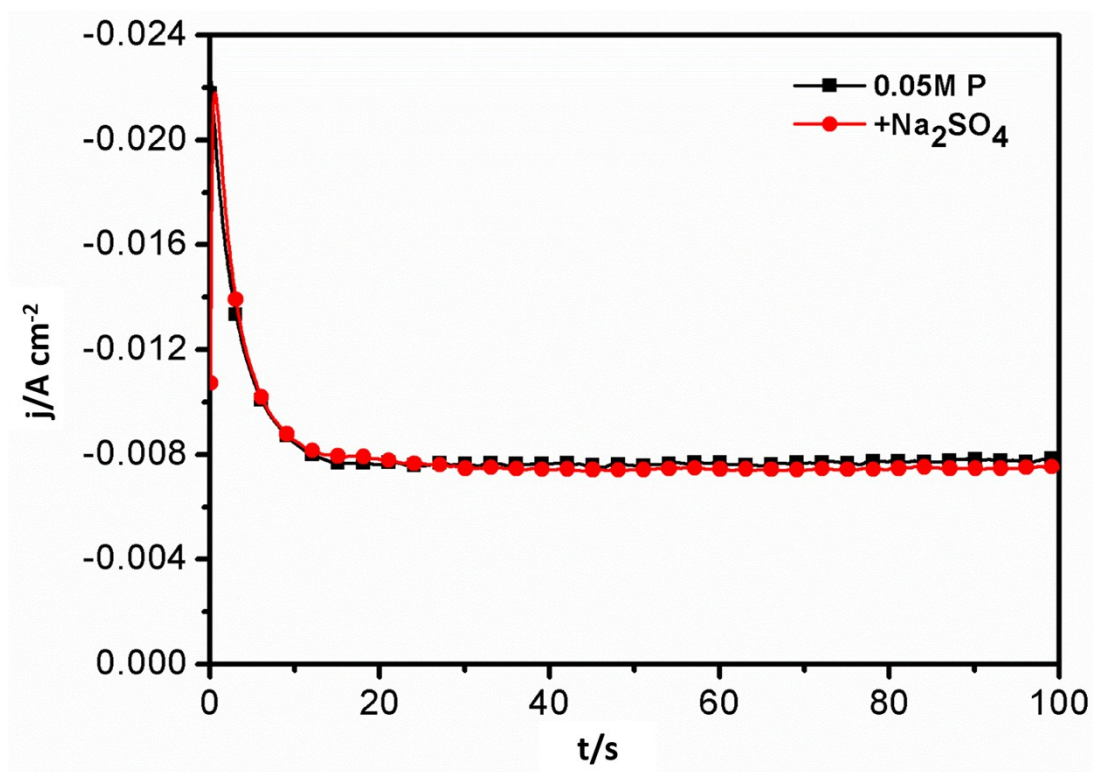
ESI 1 The schematic diagram of the three-electrode electrochemical cell set-up. The low alloy steel working electrode is sealed by the Polytetrafluoroethylene (PTFE) supporter and the area exposed to the solution is 1cm ² . The saturated Ag/AgCl reference electrode is placed into the luggin capillary filled with saturated KCl solution.	3
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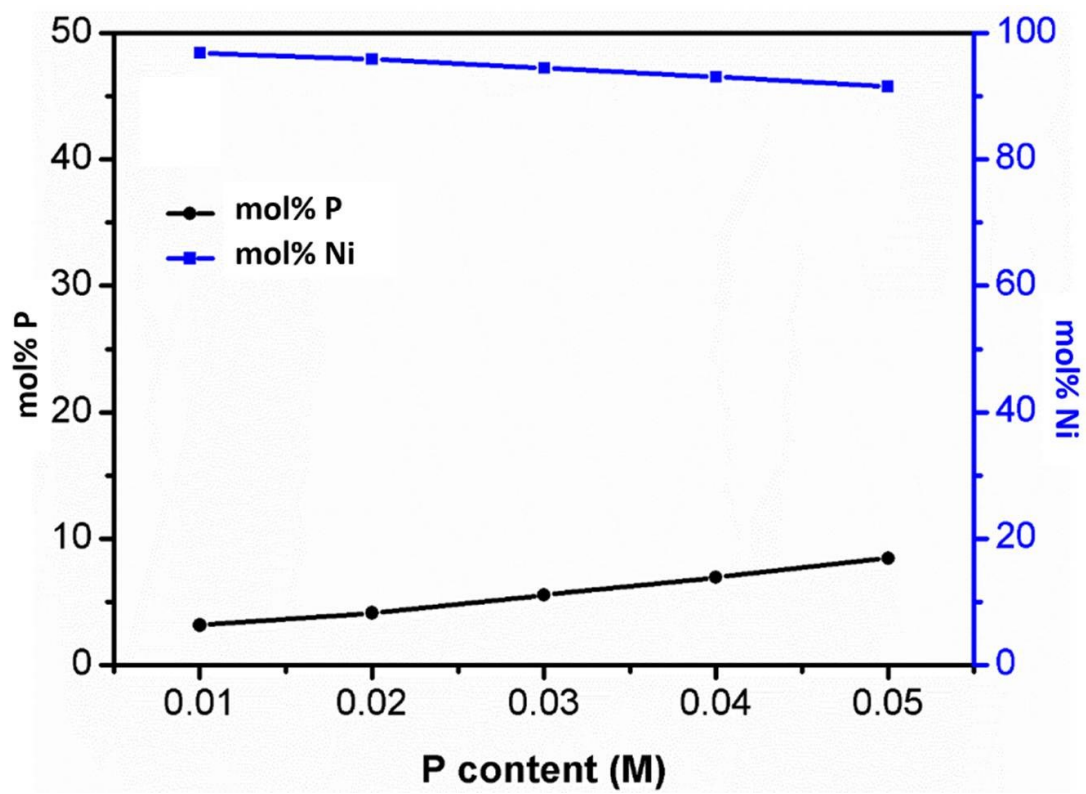
ESI 1 The schematic diagram of the three-electrode electrochemical cell set-up. The low alloy steel working electrode is sealed by the Polytetrafluoroethylene (PTFE) supporter and the area exposed to the solution is 1cm^2 . The saturated Ag/AgCl reference electrode is placed into the luggin capillary filled with saturated KCl solution.

ESI 2 table: Analysis of the current maxima for Ni-P alloy films deposited at different potential

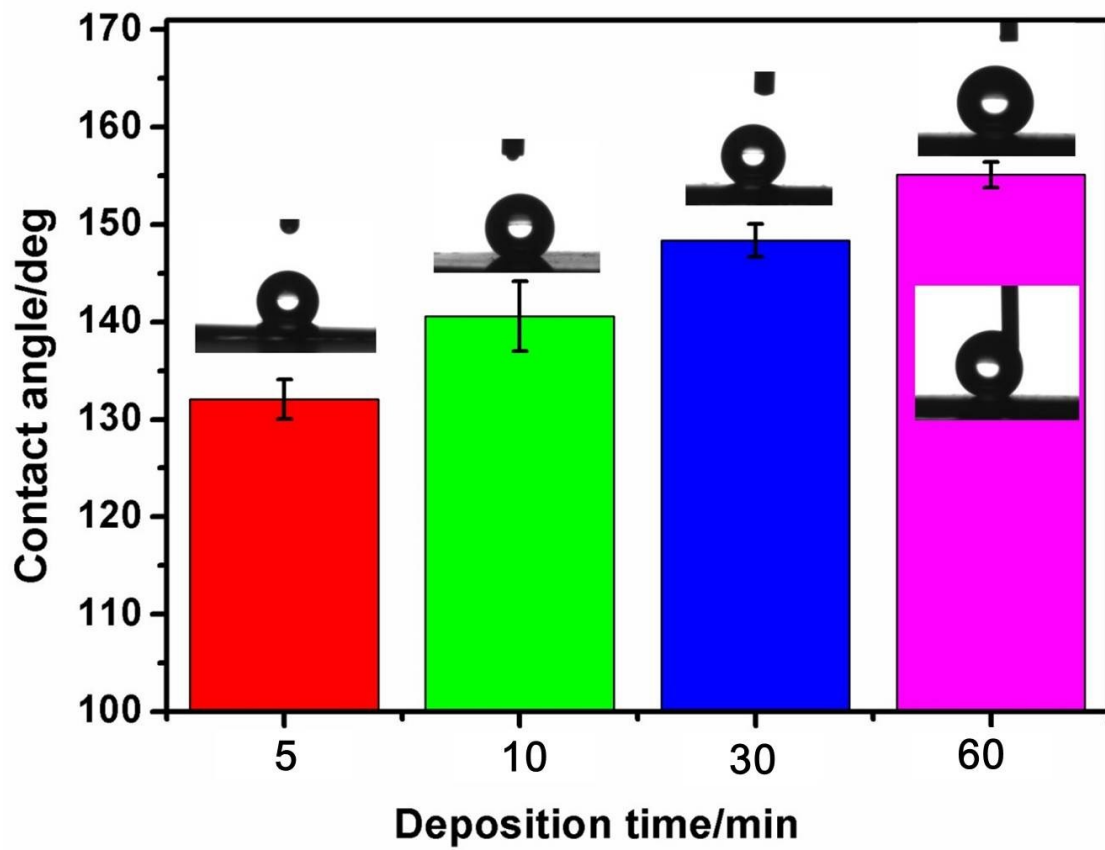
E /V	t_m /s	j_m /mA cm ⁻²	$j_m^2 t_m$ /(mA cm ⁻²) ² s
-0.1	28.7	4.45*10 ⁻³	5.68*10 ⁻⁴
-0.2	1.4	10.71*10 ⁻³	1.60*10 ⁻⁴
-0.3	0.4	31.58*10 ⁻³	3.98*10 ⁻⁴
-0.5	0.1	41.39*10 ⁻³	1.71*10 ⁻⁴



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ESI 4 Film composition of Ni-P deposit with different reducing agent in the solution.



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